*FIG. 1*

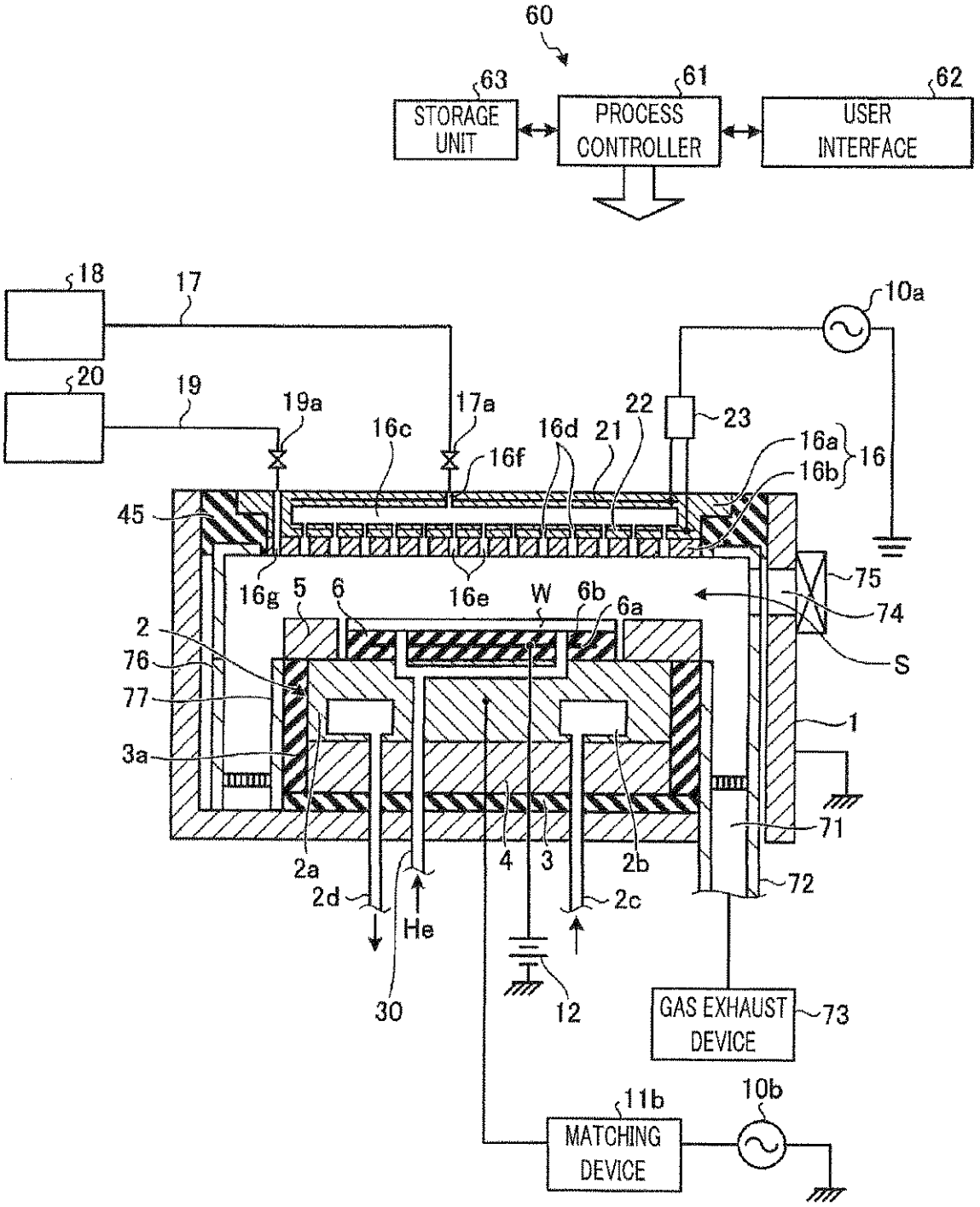

60
63
STORAGE UNIT
61
PROCESS CONTROLLER
62
USER INTERFACE
18
17
10a
20
19
19a
17a
22
23
16c
16d
21
16f
16a
16b
16
45
75
16g
5
6
16e
W
6b
6a
74
2
76
S
77
1
3a
71
4
3
2b
2a
2d
2c
72
He
30
12
GAS EXHAUST DEVICE
73
11b
10b
MATCHING DEVICE

*FIG. 2*

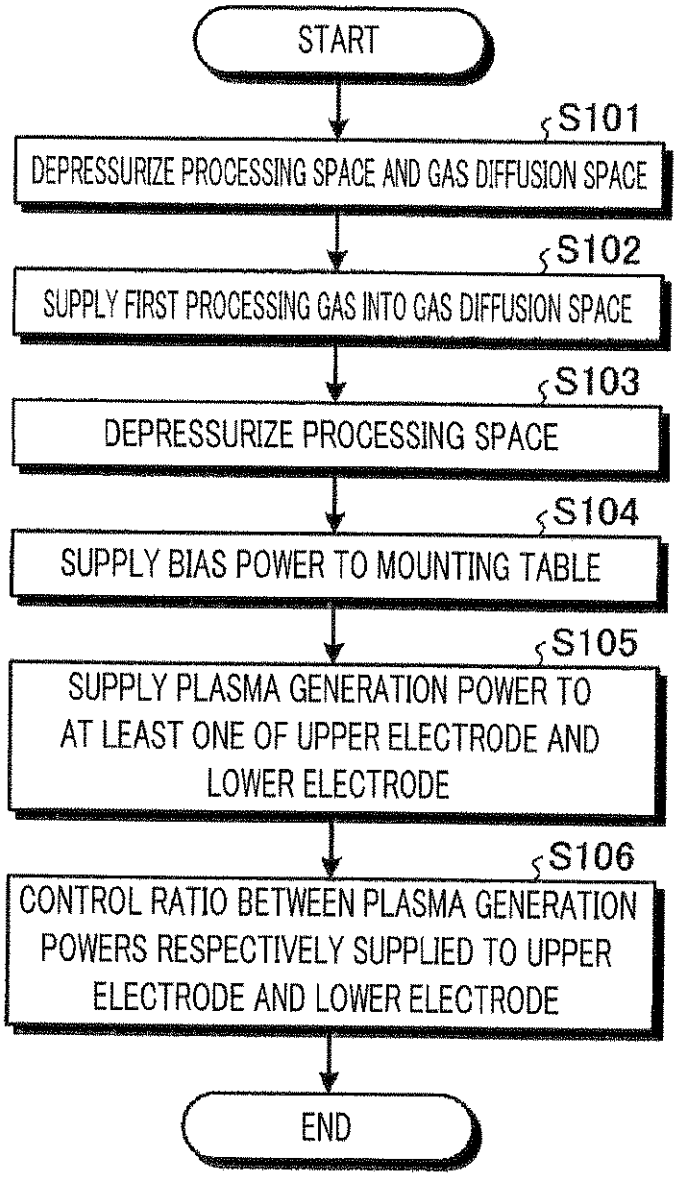

START
S101
DEPRESSURIZE PROCESSING SPACE AND GAS DIFFUSION SPACE
S102
SUPPLY FIRST PROCESSING GAS INTO GAS DIFFUSION SPACE
S103
DEPRESSURIZE PROCESSING SPACE
S104
SUPPLY BIAS POWER TO MOUNTING TABLE
S105
SUPPLY PLASMA GENERATION POWER TO AT LEAST ONE OF UPPER ELECTRODE AND LOWER ELECTRODE
S106
CONTROL RATIO BETWEEN PLASMA GENERATION POWERS RESPECTIVELY SUPPLIED TO UPPER ELECTRODE AND LOWER ELECTRODE
END

*FIG. 3*

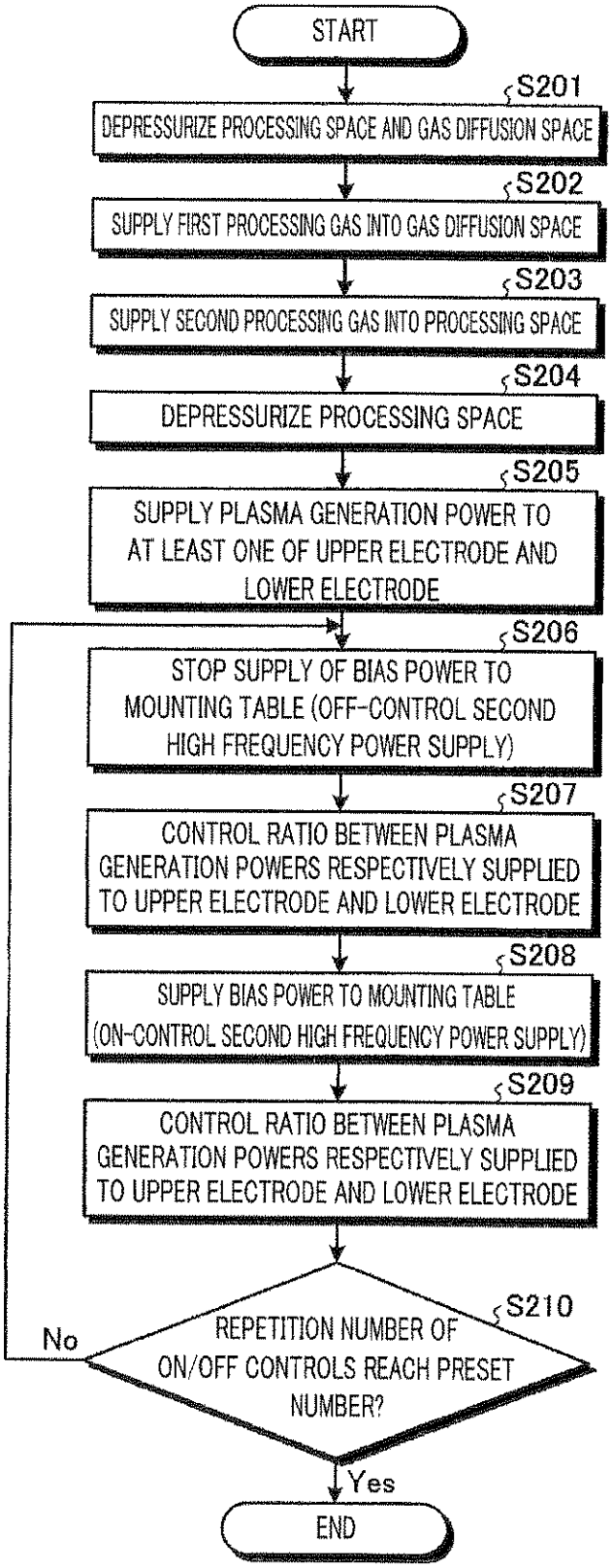

START
S201
DEPRESSURIZE PROCESSING SPACE AND GAS DIFFUSION SPACE
S202
SUPPLY FIRST PROCESSING GAS INTO GAS DIFFUSION SPACE
S203
SUPPLY SECOND PROCESSING GAS INTO PROCESSING SPACE
S204
DEPRESSURIZE PROCESSING SPACE
S205
SUPPLY PLASMA GENERATION POWER TO AT LEAST ONE OF UPPER ELECTRODE AND LOWER ELECTRODE
S206
STOP SUPPLY OF BIAS POWER TO MOUNTING TABLE (OFF-CONTROL SECOND HIGH FREQUENCY POWER SUPPLY)
S207
CONTROL RATIO BETWEEN PLASMA GENERATION POWERS RESPECTIVELY SUPPLIED TO UPPER ELECTRODE AND LOWER ELECTRODE
S208
SUPPLY BIAS POWER TO MOUNTING TABLE (ON-CONTROL SECOND HIGH FREQUENCY POWER SUPPLY)
S209
CONTROL RATIO BETWEEN PLASMA GENERATION POWERS RESPECTIVELY SUPPLIED TO UPPER ELECTRODE AND LOWER ELECTRODE
S210
REPETITION NUMBER OF ON/OFF CONTROLS REACH PRESET NUMBER?
No
Yes
END

*FIG. 4*

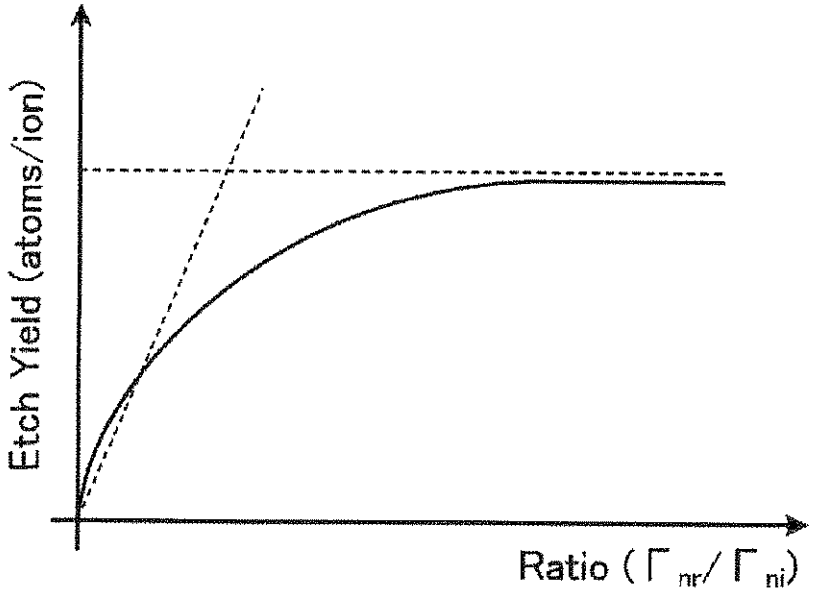
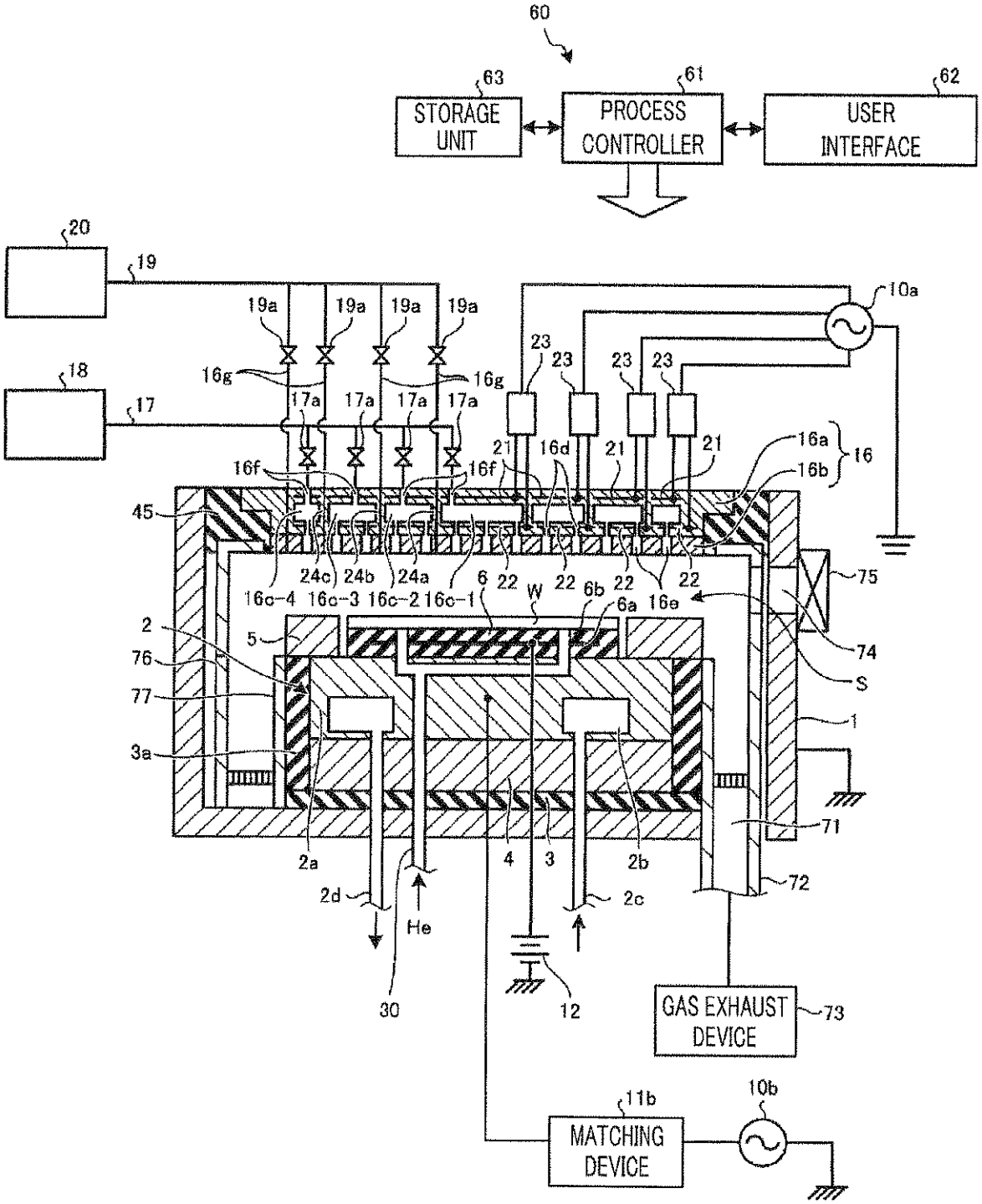


*FIG. 5*


60
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STORAGE UNIT
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PROCESS CONTROLLER
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USER INTERFACE
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16d
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16b
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10a
45
24c
24b
24a
6
22
W
6b
6a
16e
75
74
S
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72
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5
76
77
3a
2a
2d
He
30
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2b
2c
12
GAS EXHAUST DEVICE
73
11b
MATCHING DEVICE
10b
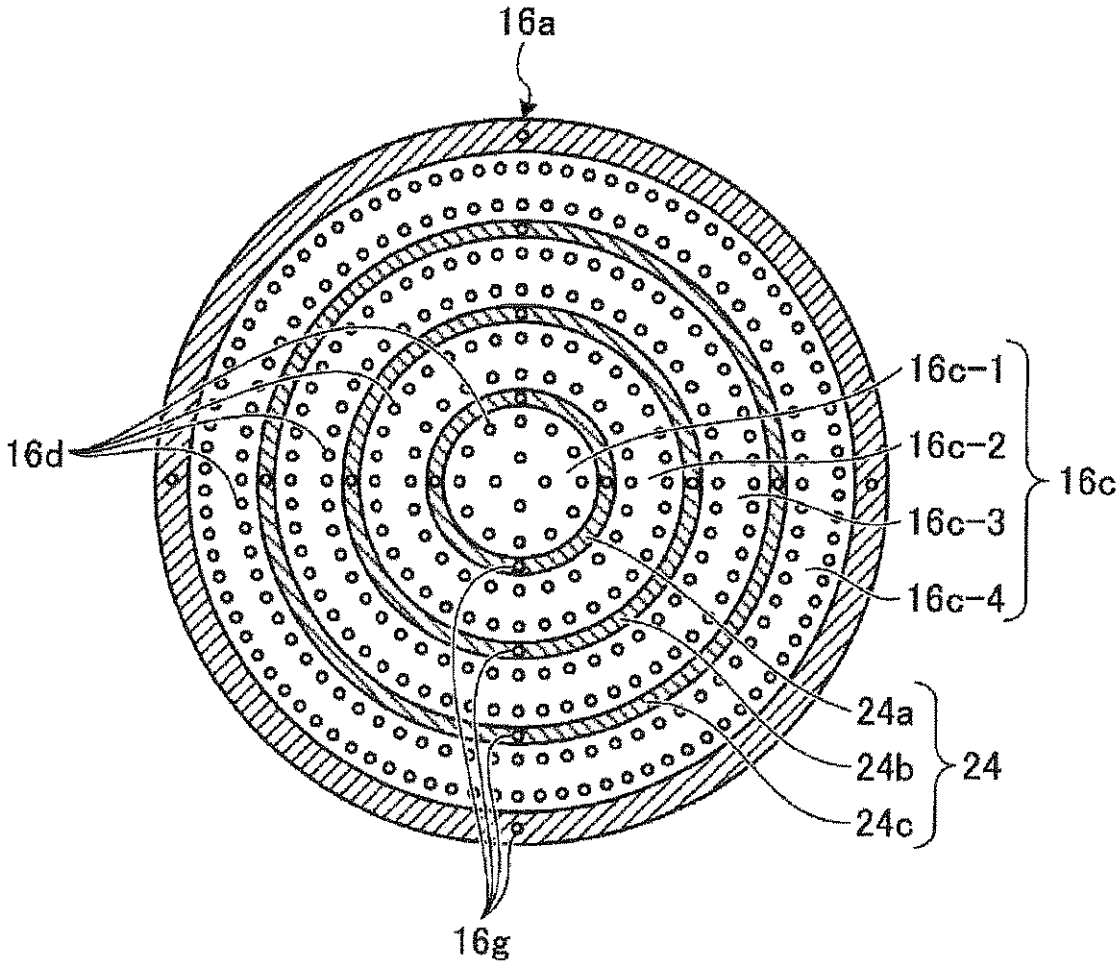
*FIG. 6*